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(54) **METHOD AND APPARATUS FOR DESIGNING PATTERNING SYSTEM BASED ON PATTERNING FIDELITY**

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See application file for complete search history.

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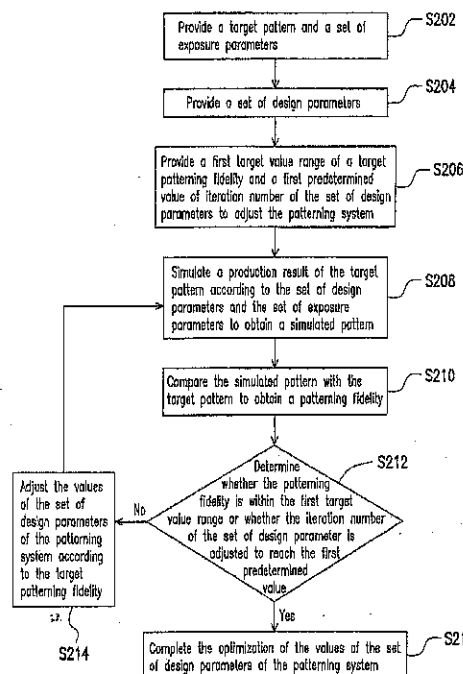
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(57) **ABSTRACT**

A method which directly incorporates patterning fidelity into the design of a patterning system is provided. A production result of a target pattern is simulated according to a set of design parameters to obtain a simulated pattern. The target pattern is compared with the simulated pattern to obtain a patterning fidelity, and the values of the set of design parameters of the patterning system are adjusted according to a target patterning fidelity to optimize the values of the set of design parameters of the patterning system.

8 Claims, 3 Drawing Sheets



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